

INFORMATION DISCLOSURE CITATION
(Use several sheets if necessary)

Docket Number (Optional)

2003US301/CIP

Application Number

10/658,840

Applicant(s)

Ralph R. DAMMEL et al.

Filing Date

December 17, 2003

Group Art Unit

1756

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
JSI		6,048,661	4/11/2000	Nisbi et al.			
JSI		6,548,219	4/15/2003	Ito et al.			

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EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE

FOREIGN PATENT DOCUMENTS

REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						YES	NO

OTHER DOCUMENTS

(Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER

DATE CONSIDERED

3/2005

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PAGE 4/4 * RCVD AT 11/15/2004 11:44:21 AM [Eastern Standard Time] * SVR:USPTO-EFXRF-1/0 * DNIS:8729306 * CSID:908 429 3650 * DURATION (mm-ss):01-32 1

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Docket Number (Optional)

2003US301/CIP

Application Number

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Applicant(s)

Ralph R. Dammel et al

Filing Date

September 9, 2003

Group Art Unit

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U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
JH		6,210,859 B1	04/03/2001	Hyun Pyo Jeon et al			
JH		6,274,286 B1	08/14/2001	Jun Hatakeyama et al			

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	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO
JH		WO 95/33753	12/14/1995	Europe				
JH		DE2460537	07/18/1975	Germany (to be sent later)				

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

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*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
js		2002/0061464 A1	5/23/2002	Aoal et al.			
js		2002/0061466 A1	5/23/2002	Lee et al.			

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	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO
js		DE 2460537						
js		GB 1496757						

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(Including Author, Title, Date, Pertinent Pages, Etc.)

js		PCT Search Report for PCT/EP2004/001194.

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JSC	2002/0061466 A1	05/23/2002	Geun Su Lee et al			
JSC	2002/0081520 A1	06/27/2002	Ratnam Soorlyakumaran et al			
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	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
JSC	EP 1 275 666 A1	01/15/2003	Europe				
JSC	WO 00/67072	11/09/2000	WIPO				
JSC	WO 00/17712	03/30/2000	WIPO				
JSC	WO 01/37047 A2	05/25/2001	WIPO				
JSC	WO 02/44811 A2	06/06/2002	WIPO				

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JSC		Cyclopolymerization and Polymers with Chain Ring Structures, ACS symposium Series 195 Edited by George Butler and Jim E. Kresta, Chapters 2, 3 and 4.
JSC		Hoang V. Tran et al, "Metal-Catalyzed Vinyl Addition Polymers for 157 nm Resist Applications. 2. Fluorinated Norbornenes: Synthesis, Polymerization and Initial Imaging Results", Macromolecules 2002, 36, 6539-6549

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[illegible]

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
JP		JP 20000376059	06/26/2002	Japan				
		WO 200198834-A1	12/27/2001	WIPO				
		GB 2 320 718 A	07/01/1998	UK				
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JS			Shun-ichi Kodama et al, "Synthesis of Novel Fluoropolymer for 157 nm Photoresists by Cyclo-polymerization", Advances in Resist Technology and Processing XIX, SPIE, Vol 4690 (2002) pages 76 - 83

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